IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

- 1. (Currently Amended) A lithographic apparatus comprising:
 - an illumination system to provide a beam of radiation;
- a support structure configured to support a patterning device, the patterning device serving to impart the beam of radiation with a pattern in its cross-section;
 - a substrate holder configured to hold a substrate;
- a projection system to project said patterned beam of radiation onto a target portion of said substrate;
- a positioning mechanism configured to position at least a portion of at least one of said support structure, said substrate table, said projection system, and said illumination system;
 - a transmitter configured to transmit electromagnetic radiation; and
- a first transducer configured to receive and convert said electromagnetic radiation into at least one of a power signal and a control signal to power at least one of a sensor, an actuator and a control unit.
- 2. (Currently Amended) The lithographic apparatus of Claim 1, wherein said electromagnetic radiation contains information and said first transducer is further configured to generate said at least one of a power signal and a control signal representing the information.
- 3. (Original) The lithographic apparatus of Claim 2, wherein said transmitter is located outside the lithographic apparatus.
- 4. (Original) The lithographic apparatus of Claim 2, wherein the lithographic apparatus further comprises an energy storage device constructed and arranged to receive said at least one of a power signal and a control signal.

5. (Original) The lithographic apparatus of Claim 2, further comprising:

a sensor configured to sense a state of at least one of said illumination system, said projection system, said patterning device, and said substrate and to produce a first electric signal representing the state, and

a second transducer configured to convert said first electric signal into electromagnetic radiation and to transmit the electromagnetic radiation,

wherein the lithographic apparatus is further arranged to co-operate with a receiver for receiving the electromagnetic radiation transmitted by the second transducer and converting it into a second electric signal.

- 6. (Original) The lithographic apparatus of Claim 5, wherein said transmitter and said receiver are integrated into a first transceiver, said first transceiver being constructed and arranged to transmit and receive said electromagnetic radiation.
- 7. (Original) The lithographic apparatus of Claim 6, wherein the transmitter and receiver are integrated into a second transceiver, the second transceiver being constructed and arranged to transmit and receive said electromagnetic radiation.
- 8. (Original) The lithographic apparatus of Claim 1, wherein the electromagnetic radiation contains information and wherein the lithographic apparatus further comprises an additional transducer that is arranged to generate a control signal representing the information.
 - 9. (Currently Amended) A lithographic apparatus comprising:
 - an illumination system to provide a beam of radiation;
- a support structure configured to support a patterning device, the patterning device serving to impart the beam of radiation with a pattern in its cross-section;
 - a substrate holder configured to hold a substrate;
- a projection system to project said patterned beam radiation onto a target portion of said substrate; and
- a wireless signaling system configured to transmit and receive informationbearing electromagnetic radiation,

wherein the information contained in said information-bearing electromagnetic radiation is used to eontrol power at least one of a sensor, an actuator and a control unit arranged in at least a portion of said at least one of said support structure, said substrate table, said projection system, and said illumination system.

- 10. (Currently Amended) The lithographic apparatus of Claim 9, wherein said wireless signaling system comprises:
 - a transmitter configured to transmit said electromagnetic radiation; and
- a first transducer configured to receive and convert said electromagnetic radiation into a first electrical signal containing the information which is used to eontrol power said at least one of a sensor, an actuator and a control unit arranged in said at least a portion of said at least one of said support structure, said substrate table, said projection system, and said illumination system.
- 11. (Original) The lithographic apparatus of Claim 10, further comprising an energy storage device constructed and arranged to receive said first electrical signal.
- 12. (Original) The lithographic apparatus of Claim 10, wherein said wireless signaling system further comprises:
- a sensor configured to sense a state of at least one of said illumination system, said projection system, said patterning device, and said substrate and to produce a second electric signal representing the state, and
- a second transducer configured to convert said second electric signal into electromagnetic radiation and to transmit the electromagnetic radiation, and
- a receiver for receiving the electromagnetic radiation transmitted by the second transducer and converting it into a third electric signal.
- 13. (Original) The lithographic apparatus of Claim 12, wherein said transmitter and said receiver are integrated into a first transceiver, said first transceiver being constructed and arranged to transmit and receive said electromagnetic radiation.
- 14. (Original) The lithographic apparatus of Claim 13, wherein the transmitter and receiver are integrated into a second transceiver, the second transceiver being constructed and arranged to transmit and receive said electromagnetic radiation.

15. (Currently Amended) A device manufacturing method, comprising: providing a substrate;

providing a beam of radiation using an illumination system;

using a patterning device to impart the beam with a pattern in its cross-section;

projecting the patterned beam of radiation onto a target portion of the

substrate; and

sensing a state of at least one of said illumination system, said projection system, said patterning device, and said substrate with a sensor;

producing an electric signal representing the state;

converting said electric signal into electromagnetic radiation by a first transducer; and

wirelessly transmitting said electromagnetic radiation to a receiver, and wireless powering said sensor.

16. (Currently Amended) A lithographic method comprising:

transmitting a beam of radiation through an illumination system;

patterning said beam of radiation with a patterning device;

projecting said patterned beam of radiation onto a substrate;

positioning at least one of said patterning device and said substrate relative to the other to enable different portions of said substrate to be imaged; and

wirelessly powering at least one of a sensor, an actuator and a control unit used in controlling at least one of said transmitting, patterning, projecting and said controlling positioning.

17. (Currently Amended) A lithographic apparatus comprising:

an illumination system to provide a beam of radiation;

a support structure that supports a patterning device, the patterning device serving to impart the beam of radiation with a pattern in its cross-section;

a substrate holder configured to hold a substrate;

a projection system that projects the patterned beam of radiation onto substrate; and

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means for wirelessly interfacing powering at least one of a sensor, an actuator and a control unit used in controlling with at least one of said illumination system, said support structure, said substrate holder and said projection system.

- 18. (New) The lithographic method of Claim 16, further comprising wirelessly controlling at least one of said transmitting, patterning, projecting and said positioning.
- 19. (New) The lithographic apparatus of Claim 17, further comprising means for wirelessly interfacing with at least one of said illumination system, said support structure, said substrate holder and said projection system.

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IN THE DRAWING(S):

The attached sheet of drawing includes changes to Figure 1. This sheet replaces the original sheet showing Figure 1. In Figure 1, element "BD" is added.